

# microCELL™ TLS

## On-the-Fly Cell Cutting System using Thermal Laser Separation

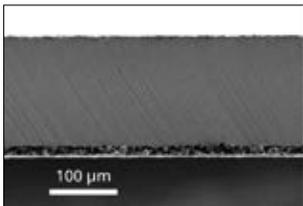
3D-Micromac's microCELL™ TLS is a highly productive laser system for separation of standard silicon solar cells into half cells. The microCELL™ TLS meets cell manufacturers' demands by retaining the mechanical strength of the cut cells. The ablation free process guarantees an outstanding edge quality. Laser processing on-the-fly and an innovative handling concept enable maximum throughput and yield in the full-scale manufacturing of crystalline half cells.

microCELL™ TLS offers:

- On-the-fly laser processing with unbeatable cost-benefit ratio
- One-pass contactless dicing process
- High throughput > 3,800 wph on single lane
- Dicing speed up to 300 mm/sec
- Low cost of ownership and CAPEX
- Inline integration into existing production lines



# microCELL™ TLS - System Configuration



TLS cleaving edge of a polycrystalline solar cell

## Configuration packages

### Stand-alone

- Two working areas on single lane for initial scribing and TLS cleaving
- Handler-tool-in for full cells and handler-tool-out for half cells

### Inline

- Two working areas on single lane for initial scribing and TLS cleaving
- Inline system for complete integration into existing production lines

### Options

- Breakage control / NIO discharge
- RFID reader
- Data matrix reader (DMC)
- Wafer buffer system
- MES system
- Loading- and unloading handling as on customer specification

Wafer size	<ul style="list-style-type: none"> <li>• 156 x 156 mm<sup>2</sup></li> <li>• Other sizes on request, square and pseudo-square shapes possible</li> </ul>
Throughput	<ul style="list-style-type: none"> <li>• &gt; 7,600 half cells on single lane at 300 mm/s</li> </ul>
Cleavage pattern	<ul style="list-style-type: none"> <li>• Half cells</li> <li>• Quarter cells</li> <li>• Other pattern on request</li> </ul>
Laser sources	<ul style="list-style-type: none"> <li>• Standard setup: two laser sources</li> <li>• Scribe laser 1064 nm</li> <li>• TLS laser 532 nm</li> </ul>
Laser processing	<ul style="list-style-type: none"> <li>• On-the-fly</li> </ul>
Beam delivery unit	<ul style="list-style-type: none"> <li>• Beam delivery unit including two processing heads for initial scribing and TLS cleaving</li> </ul>
Active alignment	<ul style="list-style-type: none"> <li>• Wafer alignment via sensor system</li> </ul>
Handling/positioning system	<ul style="list-style-type: none"> <li>• Continuously running transport belt</li> </ul>
Loading/unloading	<ul style="list-style-type: none"> <li>• Automatic loading and unloading of wafer via cassette/magazine system</li> <li>• Inline integration possible</li> </ul>
Dimensions	<ul style="list-style-type: none"> <li>• Approx. 1,865 x 1,800 x 2,000 mm<sup>3</sup> (L x W x H)</li> </ul>

Changes in accordance to technical progress are reserved.